

KMPR 1050 – run sheet

Kayaku Microchem (MicroChem)

nanyte.com/photoresists/kmpr-1050 · last updated 2026-07-26

Thickness: 34–115 μm

Softbake: 100 °C · hotplate

Exposure dose – dose by film thickness

Film thickness	Dose
5–11 μm	235–335 mJ/cm^2
12–20 μm	355–485 mJ/cm^2
21–30 μm	500–645 mJ/cm^2
31–55 μm	665–1055 mJ/cm^2
56–80 μm	1070–1465 mJ/cm^2

Post-exposure bake: 100 °C

Develop: Developer 2.38% TMAH (0.26N) aqueous alkaline developer (primary); SU-8 Developer (solvent-based) is also usable as an alternative · Dilution 2.38% TMAH (0.26N), used at this standard concentration (not diluted from a stock in the document) · Rinse DI water, ~20 s spray rinse, then filtered air/N₂ dry (TMAH path). If the optional SU-8-developer alternative is used instead, rinse is ~10 s fresh developer spray then ~10 s IPA spray, per the SU-8-developer note. · Method immersion